PART ONE: General description					
needles Process name Udo Lang Author	Process Code Contact Information (Email)	07/19/00 Last Update			
Silicon etching. General description of process					

PART TWO: Details

RIE Etching			
Pressure Set	185	Oxygen Set	0
RF Power Set	105	CHF3 Set	0
End Point Set	900	SF6 Set	55
Process Time	47		
Base Pressure Set	min 150		

PART THREE: General Comments